

Notice of Allowability	Application No.	Applicant(s)	
	10/796,754	HWANG ET AL.	
	Examiner Su C. Kim	Art Unit 2823	

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address--

All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. **THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS.** This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.

1. This communication is responsive to 01/06/2006.
2. The allowed claim(s) is/are 1-17.
3. Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
 - a) All b) Some* c) None of the:
 1. Certified copies of the priority documents have been received.
 2. Certified copies of the priority documents have been received in Application No. _____.
 3. Copies of the certified copies of the priority documents have been received in this national stage application from the International Bureau (PCT Rule 17.2(a)).

* Certified copies not received: 02/23/2006.

Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application.
THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.

4. A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.
5. CORRECTED DRAWINGS (as "replacement sheets") must be submitted.
 - (a) including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached
 - 1) hereto or 2) to Paper No./Mail Date _____.
 - (b) including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date _____.

Identifying indicia such as the application number (see 37 CFR 1.84(c)) should be written on the drawings in the front (not the back) of each sheet. Replacement sheet(s) should be labeled as such in the header according to 37 CFR 1.121(d).
6. DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.

Attachment(s)

1. Notice of References Cited (PTO-892)
2. Notice of Draftperson's Patent Drawing Review (PTO-948)
3. Information Disclosure Statements (PTO-1449 or PTO/SB/08),
Paper No./Mail Date _____
4. Examiner's Comment Regarding Requirement for Deposit
of Biological Material
5. Notice of Informal Patent Application (PTO-152)
6. Interview Summary (PTO-413),
Paper No./Mail Date _____.
7. Examiner's Amendment/Comment
8. Examiner's Statement of Reasons for Allowance
9. Other _____.

REMARK / ARGUMENT

1. By the response of Advisory Office Action mailed on 12/28/2005, Applicant filed Request for Continued Examination ('RCE') on 01/06/2006.

2. The Examiner suggests filing a **certified copy of Foreign Priority Document** under 35 U.S.C 119 (a-d) conditions to maintain earliest effective filing date as applicant claimed.

DETAILED ACTION

Allowable Subject Matter

3. Claims 1-17 are allowed over prior art.

The following is an examiner's statement of reasons for allowance:

4. Pertaining claims 1-4, the prior art fails to teach recessing a region of the isolation layer and exposing a portion of the substrate of first conductivity type under the impurity-diffused region of second conductivity type; and forming a salicide layer on a surface of the impurity-diffused region and also forming salicide layer on a surface of the exposed portion of the substrate for first conductivity type as claimed in independent claim 1.

5. Pertaining claims 5-11, the prior art fail to teach patterning the device isolation layer to form a recess in the device isolation layer that exposes a portion of the

substrate of first conductivity type adjacent the source/drain region at one side of the gate pattern; and siliciding a surface of the source/drain region of second conductivity type and a surface of the substrate of the first conductivity type exposed by the recess as claimed in independent claim 5.

6. Pertaining claims 12-17, the prior art fails to teach patterning the device isolation layer to form first and second recesses;

the first recess exposing a portion of the N-type region of the substrate adjacent to the P-type source/drain region at one side of the first gate pattern;

the second recess to exposing a portion of the P-type region of the substrate adjacent to the N-type source/drain region at one side of the second gate pattern; and

siliciding the exposed portion of the N-type and P-type regions facing respective first and second recesses; and siliciding surfaces of the N-type and P-type source/drain regions of respective second and first active regions as claimed in independent claim 12.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably

accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

7. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Jang et al. (Kr 2001-0065747)

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Su C. Kim whose telephone number is (571) 272-5972. The examiner can normally be reached on Monday - Thursday, 9:00AM to 7:00PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Matthew S. Smith can be reached on (571) 272-1907. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).



W. DAVID COLEMAN
PRIMARY EXAMINER